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AMENDMENT TRANSMITTAL LETTER				Docket No. 0171-1098PUS1
Application No. 10/849,197-Conf. #7290	Filing Date May 20, 2004	Examiner J. S. Y. Chu	Art Unit 1752	
Applicant(s): Takeru WATANABE et al.				
Invention: BASIC COMPOUND, RESIST COMPOSITION AND PATTERNING PROCESS				
MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450				
Transmitted herewith is an amendment in the above-identified application.				
The fee has been calculated and is transmitted as shown below.				
CLAIMS AS AMENDED				
	Claims Remaining After Amendment	Highest Number Previously Paled	Number Extra Claims Present	Rate
Total Claims	15	- 20 =		X
Independent Claims	9	- 9 =		X
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>				
Other fee (please specify):				
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:				0.00
<input checked="" type="checkbox"/> Large Entity <input type="checkbox"/> Small Entity				
<input checked="" type="checkbox"/> No additional fee is required for this amendment.				
<input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____. A duplicate copy of this sheet is enclosed.				
<input type="checkbox"/> A check in the amount of \$ _____ to cover the filing fee is enclosed.				
<input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached.				
<input checked="" type="checkbox"/> The Director is hereby authorized to charge and credit Deposit Account No. <u>02-2448</u> as described below. A duplicate copy of this sheet is enclosed.				
<input checked="" type="checkbox"/> Credit any overpayment.				
<input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.				
Dated: <u>July 8, 2005</u>				
Gerald M. Murphy, Jr. Attorney Reg. No.: 28,977				
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Docket No.: 0171-1098PUS1
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Takeru WATANABE et al.

Application No.: 10/849,197

Confirmation No.: 7290

Filed: May 20, 2004

Art Unit: 1752

For: **BASIC COMPOUND, RESIST COMPOSITION
AND PATTERNING PROCESS**

Examiner: J. S. Y. Chu

REPLY UNDER 37 C.F.R. 1.111

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

July 8, 2005

Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated June 10, 2005, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.